

Nanofab Training Requirements

Tool ID	Description	Room	Active CNS Enrollment	LISE/CNS Safety Training	Cleanroom Orientation	Cleanroom Wet Bench Training	Cleanroom Resist Spinner Training
ALD1	Atomic Layer Deposition System, Cambridge Nanotech	G07 Dry Bay	x	x	x		
CVD5-8	Furnace, 4 tube stack, Tystar	G07 Dry Bay	x	x	x	x	
CVD9-12	Furnace, 4 tube stack, Tystar	G07 Dry Bay	x	x	x	x	
CVD2	PECVD, NEXX	G07 Dry Bay	x	x	x		
CVD3	PECVD, STS	G07 Dry Bay	x	x	x		
RIE6	Reactive Ion Etcher, NEXX	G07 Dry Bay	x	x	x		
RIE1	Reactive Ion Etcher, South Bay	G07 Dry Bay	x	x	x		
RIE8	REACTIVE ION ETCHER, STS	G07 Dry Bay	x	x	x		
RIE7	Reactive Ion Etcher, Unaxis	G07 Dry Bay	x	x	x		
SP2	SPUTTERING SYSTEM, AJA	G07 Dry Bay	x	x	x		
SB06	Wet Bench, develop, SB06	G07 Ebeam	x	x	x	x	
SB07	Wet Bench, Spin, SB07	G07 Ebeam	x	x	x	x	x
EL4	EBEAM LITHOGRAPHY SYSTEM, Elionix	G07 Ebeam suite 1 (back)	x	x	x	x	x
EL3	Ebeam Lithography System, JEOL 7000	G07 Ebeam suite 2	x	x	x	x	x
EL1	EBeam Lithography System, Raith	G07 Ebeam suite 3 (front)	x	x	x	x	x
MET2	4 point probe resistivity tester	G07 Metrology	x	x	x		
SPM5	Atomic Force Microscope, Veeco	G07 Metrology	x	x	x		
ES2	ELLIPSOMETER, Gaertner	G07 Metrology	x	x	x		
ES-1	Ellipsometer, Spectroscopic, Woollam	G07 Metrology	x	x	x		

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CE1	PARAMETER ANALYZER, Agilent	G07 Metrology	x	x	x		
PB-1	Probe Station, Signatone	G07 Metrology	x	x	x		
PL2	PROFILOMETER, OPTICAL, Wyko	G07 Metrology	x	x	x		
PL1	Profilometer, Stylus, AlphaStep	G07 Metrology	x	x	x		
	PROFILOMETER, STYLUS, Dektak	G07 Metrology	x	x	x		
	PROFILOMETER, STYLUS, Dektak	G07 Metrology	x	x	x		
MET1	Stress Measurement System	G07 Metrology	x	x	x		
MW1	Hiedelberg Laser Mask Generator	G07 Photo Bay	x	x	x		
	Hot Plate Rack Tower	G07 Photo Bay	x	x	x	x	
OL4	MASK ALIGNER, MA6	G07 Photo Bay	x	x	x	x	
OL3	MASK ALIGNER, MJB3	G07 Photo Bay	x	x	x	x	
OL5	Mask Aligner, MJB4	G07 Photo Bay	x	x	x	x	
SB03	Wet Bench, develop SU8, SB03	G07 Photo Bay	x	x	x	x	
AB03	Wet Bench, develop, AB03	G07 Photo Bay	x	x	x	x	
SB05	Wet Bench, Spinner SU8, SB05	G07 Photo Bay	x	x	x	x	x
SB04	Wet Bench, spinner, SB04	G07 Photo Bay	x	x	x	x	x
EE4	e-beam evaporator, Denton, EE4	G07 PVD	x	x	x		
EE2	E-beam evaporator, Edwards, EE2	G07 PVD	x	x	x		
EE1	e-beam evaporator, Lesker, EE-1	G07 PVD	x	x	x		
EE3	e-beam evaporator, Sharon, EE3	G07 PVD	x	x	x		

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TE1	Evaporator, Thermal, Keyhigh, TE1	G07 PVD	x	x	x		
TE3	Evaporator, Thermal, Sharon, TE3	G07 PVD	x	x	x		
TE4	Evaporator, Thermal, Sharon, TE4	G07 PVD	x	x	x		
TE5	Evaporator, Thermal, Sharon, TE5	G07 PVD	x	x	x		
TE5	Evaporator, Thermal, Sharon, TE5	G07 PVD	x	x	x		
RTP1	Rapid Thermal Annealer, Jipelec	G07 PVD	x	x	x		
RTP2	Rapid Thermal Annealer, MPTC	G07 PVD	x	x	x		
RIE9	Plasma Cleaner, Anatech	G07 Wet Bay	x	x	x		
RIE5	Plasma Cleaner, Technics	G07 Wet Bay	x	x	x		
SRD-1	Spin Rinse Dryer	G07 Wet Bay	x	x	x	x	
RIE4	UV/Ozone Cleaning System	G07 Wet Bay	x	x	x		
AB01	Wet Bench, Acid, AB01	G07 Wet Bay	x	x	x	x	
SB01	Wet Bench, lift-off, SB01	G07 Wet Bay	x	x	x	x	
AB02	Wet Bench, RCA, AB02	G07 Wet Bay	x	x	x	x	
SB02	Wet Bench, solvent clean, SB02	G07 Wet Bay	x	x	x	x	
SW-3	Fiber splicing kit, Fujikura	G12	x	x			
FCB-1	Flip Chip Bonder, Finetech	G12	x	x			
PB2	Probe Station, 1.5K, Lakeshore	G12	x	x			
SW2	SCRIBER, Loomis	G12	x	x			
WB1	Wire Bonder, Westbond	G12	x	x			
CVD4	Furnace, Lindberg	G27	x	x			

1 Required for certain projects.